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## NOVELLUS' HCM® IONX™ XL Ta(N) BARRIER TECHNOLOGY ENABLES 3X/2Xnm MEMORY TRANSITION TO COPPER

San Jose, Calif. - May 27, 2009 - Ten years after the introduction of copper metallization for logic device manufacturing, [Physical Vapor Deposition](#) (PVD) copper barrier-seed and copper [electrochemical deposition](#) (ECD) are now being used for the production of DRAM and Flash memory chips. The memory transition from aluminum metallization to [copper interconnects](#) is being driven by the technological challenges associated with device scaling and the need to reduce memory chip manufacturing cost.

One of the key components of a copper memory interconnect is the PVD tantalum nitride (Ta(N)) barrier layer that provides the necessary copper diffusion resistance, as well as wettability for the subsequent copper [seed layer](#). For memory manufacturers, the challenge comes with depositing this barrier film in advanced device structures that can possess up to 30 percent smaller critical dimensions (CD) than those found in logic applications. For these aggressive geometries, planar PVD is limited by shadowing effects that can cause incomplete film coverage due to overhang at the top corner of the trench or via, in turn leading to inadequate copper fill and yield loss. Some planar PVD barrier solutions are investigating the incorporation of more expensive CVD layers to mitigate these effects. Compounding these challenges is the fact that Ta(N) barriers also need to be very thin (less than 120Å in the field) in order to minimize the volume fraction of high resistivity Ta(N) relative to low resistivity copper within the feature.

To address the challenges discussed above, Novellus (NASDAQ: NVLS) has developed the IONX XL (eXtended Life) Ta(N) barrier process for the 3x/2xnm memory node, based on Novellus' PVD [Hollow Cathode Magnetron](#) (HCM) deposition technology. This PVD-only barrier process deposits high quality films with excellent step coverage for high aspect ratio memory structures. The conformal Ta(N) films deposited with this technology are the result of an increased plasma density and more effective control of the ionized flux that reaches the wafer surface. Figure 1 shows a thin, highly conformal IONX XL Ta(N) barrier layer deposited into a 3nm memory device trench with no top corner overhang. Not only does this robust copper barrier process meet the technical challenges of advanced memory, but it also results in a 40 percent reduction in the tantalum Cost of Consumables (CoC) compared to competitive market offerings. A 100,000 wafer-starts-per-month memory megafab using two levels of metal can save approximately \$1M a year in consumable costs through more efficient utilization of the tantalum target material.

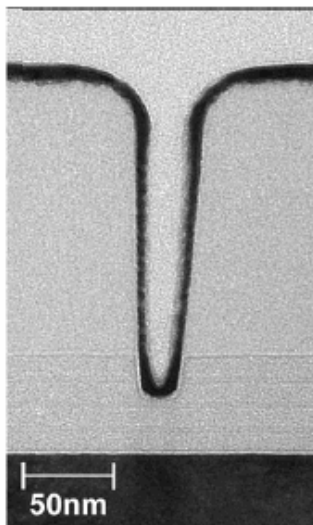


Figure 1: 3X nm IONX XL Ta(N) barrier.

"As memory technology transitions to copper interconnects, the 3x/2xnm device dimensions are placing stringent technical and cost requirements on the Ta(N) barrier layer," said Dr. Wai-Fan Yau, general manager for Novellus' Integrated Metals Business Unit. "The new IONX XL barrier film meets these advanced technical demands and also provides a significant reduction in consumable costs."

For more information on Novellus' IONX XL Ta(N) barriers, go to [www.NovellusTechNews.com](http://www.NovellusTechNews.com).

**About Novellus' PVD Copper Barrier/Seed Technology:**

For copper barrier-seed applications, Novellus' INOVA® NExT PVD system features a patented hollow cathode magnetron (HCM) IONX source technology, providing highly conformal barrier films and scalable seed layers that extend PVD technology to the 3x technology node and beyond.

**About Novellus:** Novellus Systems, Inc. (NASDAQ: NVLS) is a leading provider of advanced process equipment for the global semiconductor industry. The company's products deliver value to customers by providing innovative technology backed by trusted productivity. An S&P 500 company, Novellus is headquartered in San Jose, Calif. with subsidiary offices across the globe. For more information, please visit [www.novellus.com](http://www.novellus.com)